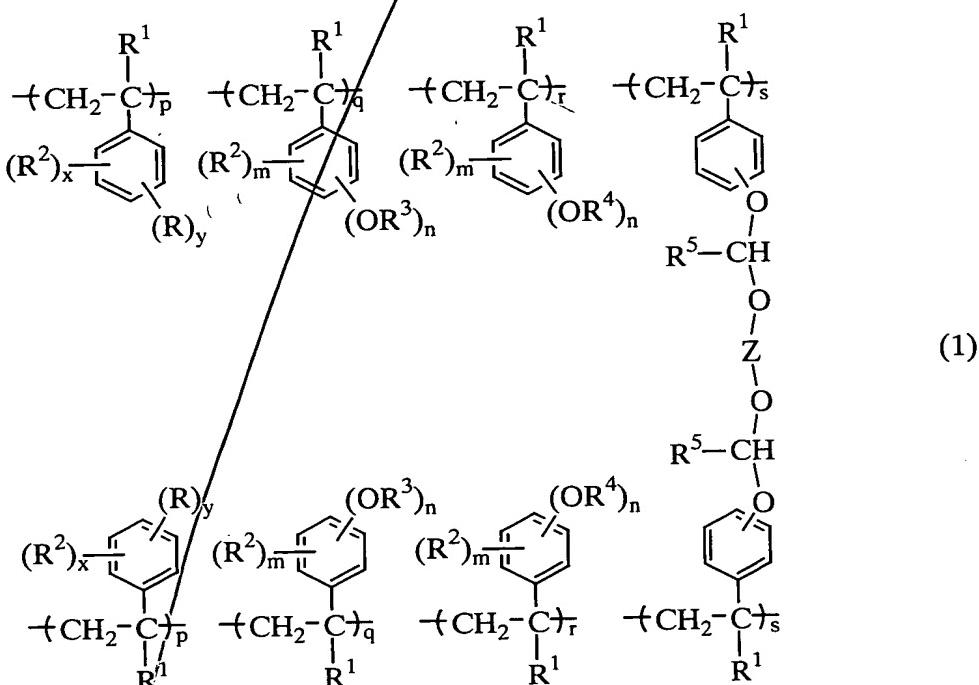


SAB

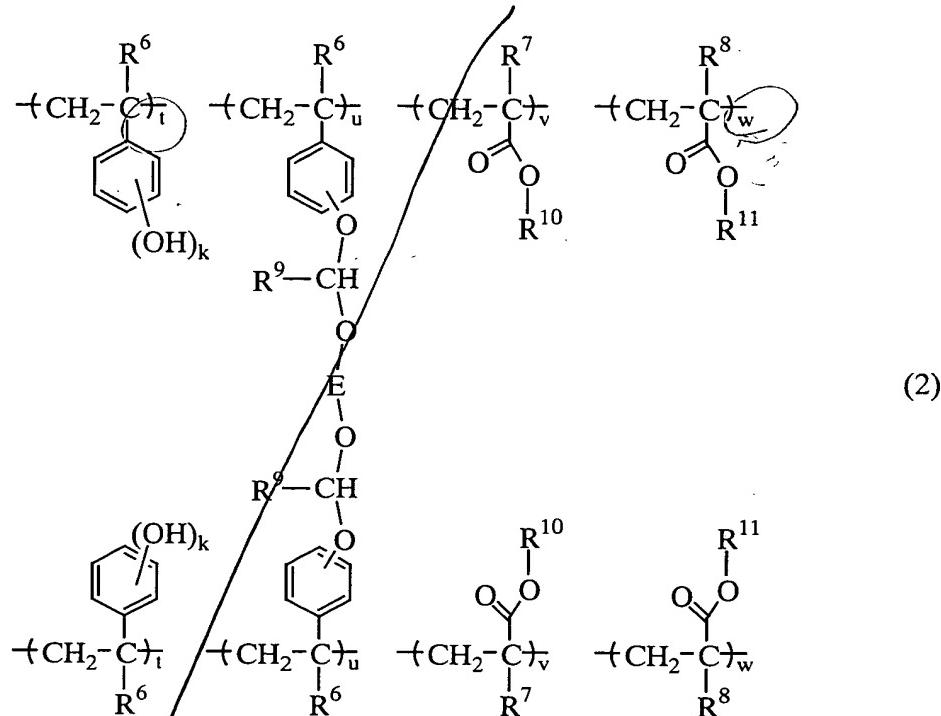
CLAIMS:

1. A chemical amplification type resist composition comprising a polymeric mixture of a polymer comprising recurring units of the general formula (1) and having a weight average molecular weight of 1,000 to 500,000 and a polymer comprising recurring units of the general formula (2) and having a weight average molecular weight of 1,000 to 500,000.



10 wherein R is a hydroxyl group or a OR³ group, R¹ is hydrogen or methyl, R² is a straight, branched or cyclic alkyl group of 1 to 8 carbon atoms, R³ and R⁴ each are an acid labile group, R⁵ is methyl or ethyl, Z is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms, x is 0 or a positive integer, y is a positive integer, satisfying x+y ≤ 5, m is 0 or a positive integer, n is a positive integer, satisfying m+n ≤ 5, p, q, r and s each are 0 or a positive number, satisfying p+q+r+s = 1.

*Bald
old*



wherein R⁶, R⁷ and R⁸ each are hydrogen or methyl, R⁹ is methyl or ethyl, E is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms, R¹⁰ is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms, which may contain an oxygen or sulfur atom, R¹¹ is a tertiary alkyl group of 1 to 20 carbon atoms, k is 0 or a positive integer of up to 5, t and w each are a positive number, u and v each are 0 or a positive number, either one of u and v is not equal to 0, satisfying t+u+v+w = 1.

2. A chemical amplification type, positive resist composition comprising

- (A) an organic solvent,
15 (B) the polymeric mixture of claim 1 as a base resin,
and
(C) a photoacid generator.

3. A chemical amplification type, positive resist composition comprising

- (A) an organic solvent,
(B) the polymeric mixture of claim 1 as a base resin,

- (C) a photoacid generator, and
(D) a dissolution regulator.

SuB
CAT
4. The resist composition of claim 2 or 3, further
5 comprising (E) a basic compound.

Add B2